1. Title:	EUV Resist Materials Properties and Performance
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3. Abstract body:

The development of EUV resists faces many challenges which are being addressed through several programs designed to both demonstrate current capability and provide direction for future development. Intel's material target specifications for EUV resists including resolution, line width roughness, photo sensitivity and outgassing will be reviewed and areas where acceleration is required to meet the Intel roadmap will be highlighted.. Results will be presented from several novel materials projects intended to advance the capabilities of EUV resists, including attempts to engineer photo-acid trajectory through pre-organization of functionality within the resist matrix through the use of self assembled monolayers, host-guest systems and pre-organized ion pairs.